

REMARKS

Claims 11-25, 27-40, 52-55, 57, 59 and 60 are pending in this application. Claims 11-22, 52-55 and 60 are withdrawn from consideration as being drawn to a non-elected species. Rejoinder of claims 11-22, 52-55 and 60 is respectfully requested. By this Amendment, claims 23-25, 31, 36, 39, 40, 57 and 59 are amended and claim 35 is canceled without prejudice to or disclaimer of the subject matter disclosed therein. Reconsideration of the application is respectfully requested.

The Office Action rejects claims 23-25, 27-40, 57 and 59 under 35 U.S.C. §112, second paragraph. The claims are amended to overcome the rejection by canceling the recitation of "forming a plurality of film forming regions which are aligned in a predetermined pattern." Accordingly, withdrawal of the rejection of the claims under 35 U.S.C. §112, second paragraph, is respectfully requested.

The Office Action rejects claims 23-25, 27-40, 57 and 59 under 35 U.S.C. §102(e) over Paz de Araujo et al. (U.S. Patent No. 6,110,531). The rejection is respectfully traversed.

In particular, Paz de Araujo fails to disclose or suggest a film forming section and a non-film forming section, as recited in independent claims 23, 25, 57 and 59.

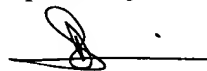
Paz de Araujo teaches a mist generated by a venturi from liquid precursors containing compounds used in chemical vapor deposition, transported in carrier gas through tubing at room temperature and passed into a heated zone where the mist droplets are gasified (Abstract). Moreover, Paz de Araujo teaches that the annealing step 632 can be performed either before or after the patterning of the capacitor 772 (col. 15, lines 46-48), and also teaches that the capacitor, which is formed by the first electrode 758, the ferroelectric material 760 and the second electrode 777, is formed by patterning the first electrode 758, the ferroelectric material 760 formed by chemical vapor deposition, and the second electrode 777 formed by sputtering after repeated layering (col. 15, lines 23-38). Accordingly, Paz de Araujo does not teach forming a film forming section and a non-film forming section, as recited in independent claims

23, 25, 57 and 59 because Paz de Araujo does not teach or suggest forming a portion made of a particular material having an opposite characteristic from ceramics such as a film forming section and a non-film forming section on the substrate. Support for the film forming section and the non-film forming section can be found in the specification at, for example, page 21, lines 17-24. Moreover, because Paz de Araujo does not teach a film forming section and a non-film forming section, Paz de Araujo cannot form a ceramic film in a film forming section self-alignably, without forming a mask such as a resist and patterning by etching. Accordingly, Paz de Araujo fails to disclose or suggest the features of independent claims 23, 25, 57 and 59. As such, independent claims 23, 25, 57 and 59, and their dependent claims, are patentable over Paz du Araujo. Accordingly, withdrawal of the rejection of the claims under 35 U.S.C. §102(e) is respectfully requested.

In view of the foregoing, it is respectfully submitted that this application is in condition for allowance. Favorable reconsideration and prompt allowance of claims 23-25, 27-40, 57 and 59 are earnestly solicited.

Should the Examiner believe that anything further would be desirable in order to place this application in even better condition for allowance, the Examiner is invited to contact the undersigned at the telephone number set forth below.

Respectfully submitted,



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